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APPLICATION NO.	F	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/676,295		09/30/2003	Andrea Urban	10191/3212A	8189	
26646	7590	02/08/2006		EXAMINER		
KENYON		ON LLP	AHMED, SHAMIM			
ONE BROADWAY NEW YORK, NY 10004				ART UNIT	PAPER NUMBER	
NEW Fords, IVE 1000				1765	1765	
				DATE MAILED: 02/08/200	DATE MAILED: 02/08/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

•		Application No.	Applicant(s)					
		10/676,295	URBAN ET AL.					
	Office Action Summary	Examiner	Art Unit					
		Shamim Ahmed	1765					
- The MAILING DATE of this communication appears on the cover sheet with the correspondence address - Period for Reply								
WHIC - Exter after - If NO - Failu Any	ORTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING DATE of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. It is specified above, the maximum statutory period were to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be timulated and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D (35 U.S.C. § 133).					
Status								
1)⊠	Responsive to communication(s) filed on <u>01 M</u>	ay 0125.						
2a) <u></u> ☐	This action is <b>FINAL</b> . 2b)⊠ This action is non-final.							
3)□	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is							
closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.								
Dispositi	ion of Claims							
4)⊠	4)⊠ Claim(s) <u>1-8 and 10-21</u> is/are pending in the application.							
	4a) Of the above claim(s) is/are withdrawn from consideration.							
5) Claim(s) is/are allowed.								
6)⊠	6)⊠ Claim(s) <u>1-8 and 10-21</u> is/are rejected.							
	Claim(s) is/are objected to.							
8)∐	Claim(s) are subject to restriction and/o	r election requirement.						
Applicati	ion Papers							
9)[[]	The specification is objected to by the Examine	er.	•					
10)⊠ The drawing(s) filed on <u>01 May 1125</u> is/are: a)⊠ accepted or b)⊡ objected to by the Examiner.								
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).								
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).								
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.								
Priority (	under 35 U.S.C. § 119							
12)	Acknowledgment is made of a claim for foreign	priority under 35 U.S.C. § 119(a	)-(d) or (f).					
a) ☐ All b) ☐ Some * c) ☐ None of: 1. ☐ Certified copies of the priority documents have been received.								
2. Certified copies of the priority documents have been received in Application No								
	3. Copies of the certified copies of the prior							
	application from the International Bureau							
* See the attached detailed Office action for a list of the certified copies not received.								
Attachmen		_						
	ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (PTO-948)	4)  Interview Summary Paper No(s)/Mail D						
3) 🔲 Infor	mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) or No(s)/Mail Date		Patent Application (PTO-152)					

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### **DETAILED ACTION**

## Response to Arguments

1. Applicant's arguments with respect to claims 1-21 have been considered but are moot in view of the new ground(s) of rejection.

### **Drawings**

2. The drawings were received on 11/25/05. These drawings are acceptable.

#### Terminal Disclaimer

3. The terminal disclaimer filed on 11/25/05 disclaiming the terminal portion of any patent granted on this application which would extend beyond the expiration date of copending US application serial No. 10/473,831 has been reviewed and is accepted. The terminal disclaimer has been recorded.

### Claim Rejections - 35 USC § 102

4. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 5. Claims 1-3,7-8 are rejected under 35 U.S.C. 102(b) as being anticipated by Grunwald (4,863,549).

Grunwald teaches a plasma etching process for etching a silicon body with photoresist masking layer including the step of generating the plasma, which inherently includes at least approximately ambipolar plasma by injecting high frequency power into

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the substrate via the substrate electrode (6), wherein the plasma is modulated or pulsed as a function of time (abstract and col.2, lines 43-col.3, lines 1-39).

# Claim Rejections - 35 USC § 103

- 6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 7. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).
- 8. Claims 4-6,10-15 and 18-20 are rejected under 35 U.S.C. 103(a) as being unpatentable over Grunwald (4,863,549) in view of in view of Koshimizu (5,290,383).

Grunwald discusses above in the paragraph 5 but fail to teach adding an inert gas in the plasma.

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However, in a controlled plasma etching process of silicon substrate, Koshimizu teaches the addition of inert gas into the plasma in order to stabilize the plasma (col.14, lines 29-41).

Therefore, it would have been obvious to one of ordinary skilled in the art at the time of claimed invention to combine Koshimizu's teaching into Laermer et al's process for stabilizing the plasma as taught by Koshimizu.

As to claim 10, it would have been obvious to pause the plasma pulse during the pause of the substrate pulse.

9. Claims 16-17 are rejected under 35 U.S.C. 103(a) as being unpatentable over Grunwald (4,863,549) in view of Hashimoto et al (5,779,925).

Grunwald discusses above in the paragraph 5 but fail to teach synchronizing the modulation and the low-frequency modulation with one another.

However, Hashimoto et al teach that the RF bias is synchronized with the on/off modulation in order to reduce charging damage with out lowering the through put (col.16, lines 35-42, lines 66-col.17, line 5).

Therefore, it would have been obvious to one of ordinary skilled in the art at the time of claimed invention to combine Hashimoto et al's teaching into Grunwald 's process for reducing charging damage and for improved etching precision as taught by Hashimoto et al.

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10. Claim 21 is rejected under 35 U.S.C. 103(a) as being unpatentable over Grunwald (4,863,549) in view of Dockrey (4,799,991).

Grunwald discusses above in the paragraph 5 and also teach that the under etching can be performed using SF<sub>6</sub> (col.2, lines 64-65) but fail to teach that the under etching is performed using highly oxidizing fluorine compound includes CIF<sub>3</sub>.

However, in a process of silicon etching, Dockrey teaches both the SF<sub>6</sub> and CIF<sub>3</sub> can be used as an efficient etchant for silicon (see claims 7 and 12).

Therefore, it would have been obvious to one of ordinary skilled in the art at the time of claimed invention to combine Dockrey's teaching into Grunwald 's process because both SF<sub>6</sub> and CIF<sub>3</sub> are functionally equivalent as taught by Dockrey.

### Conclusion

11. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Collins (5,888,414) teaches silicon-etching process including modulating/pulsing the plasma.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Shamim Ahmed whose telephone number is (571) 272-1457. The examiner can normally be reached on M-Thu (7:00-5:30) Every Friday Off.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine G. Norton can be reached on (571) 272-1465. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Shamim Ahmed Primary Examiner Art Unit 1765

SA February 4, 2006